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Titolo	Chemical Solution Deposition of Functional Oxide Thin Films / / edited by Theodor Schneller, Rainer Waser, Marija Kosec, David Payne
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ISBN	3-211-99311-8
Edizione	[1st ed. 2013.]
Descrizione fisica	1 online resource (801 p.)
Disciplina	660.6
Soggetti	Materials—Surfaces
	Thin films
	Physical chemistry
	Industrial engineering
	Production engineering
	Tribology
	Corrosion and anti-corrosives
	Coatings
	Surfaces and Interfaces, Thin Films
	Physical Chemistry Industrial and Production Engineering
	Tribology, Corrosion and Coatings
Lingua di pubblicazione	
Formato	Materiale a stampa
Livello bibliografico	Monografia
Note generali	Description based upon print version of record.
Nota di bibliografia	Includes bibliographical references at the end of each chapters and index.
Nota di contenuto	Introduction Solution Chemistry; Simple alskoxide based precursor systems; Carboxylate based precursor systems; Single-source precursors; Acqueos Precursor Systems; Solution Synthesis Strategies Analytical Methods; Introduction; Thermal Analysis; NMR Sepctroscopy; EXAFS; Other Methods (XRM, SEM,TEM;scattering methods at nanocrystalline films); Spin-Coating; Dip Coating; Inkjet Printing and Other Direct Writing Methods(dip point and imprint techniques); Chemical Bath Deposition; Polymer Assisted Deposition Processing and Crystallization; Thermodynamics and Heating Processes; Material Systems Dominated by Heterogeneous Nucleation;

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	Material Systems Dominated by Homogeneous Nucleation; Low Temperature Processing; Epitaxial Films; Powder Assisted Film Fabrication; UV-and E-Beam Direct Patterning of Photosensitive CSD Films; Template Controlled Growth Functions and Applications; Introduction; Integrated Capacitors; Base Metal Electrodes; Polar Oxide Films for MEMS Applications;Conducting Films and Electrodes; Transparent conducting oxides; Superconducting Films; Porous Films for Gas Sensors; Luminescent Fims Appendix; Synthesis for Standard material Systems.
Sommario/riassunto	This is the first text to cover all aspects of solution processed functional oxide thin-films. Chemical Solution Deposition (CSD) comprises all solution based thin- film deposition techniques, which involve chemical reactions of precursors during the formation of the oxide films, i. e. sol-gel type routes, metallo-organic decomposition routes, hybrid routes, etc. While the development of sol-gel type processes for optical coatings on glass by silicon dioxide and titanium dioxide dates from the mid-20th century, the first CSD derived electronic oxide thin films, such as lead zirconate titanate, were prepared in the 1980's. Since then CSD has emerged as a highly flexible and cost-effective technique for the fabrication of a very wide variety of functional oxide thin films. Application areas include, for example, integrated dielectric capacitors, ferroelectric random access memories, pyroelectric infrared detectors, piezoelectric micro- electromechanical systems, antireflective coatings, optical filters, conducting-, transparent conducting-, and superconducting layers, luminescent coatings, gas sensors, thin film solid-oxide fuel cells, and photoelectrocatalytic solar cells. In the appendix detailed "cooking recipes" for selected material systems are offered.